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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 of 2

Complete if Known	
Application Number	TO BE ASSIGNED (Divl)
Filing Date	March 8, 2002
First Named Inventor	Bruce W. Smith
Group Art Unit	2851
Examiner Name	Hung NGUYEN
Attorney Docket Number	81468.284420

jc971 U.S. PTO 10/092483 03/08/02

U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.[1]	U.S. Patent Document Number	Kind Code[2] (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
HW	1	5,627,625		Tohru Ogawa	05/06/97	
	2	5,638,211		Naomasa Shiraishi	06/10/97	
	3	3,776,633		Albert Frosch, et al	12/04/73	
	4	3,729,252		Clarence N. Nelson	04/24/73	
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HW	8	5,305,054		Akiyoshi Suzuki, et al.	04/19/94	

FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No.[1]	Foreign Patent Document Office[3]	Number[4]	Kind Code[5] (if known)	Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T[6]
HW	9	EP	0 503 472 A3	EP	Minori Noguchi	09/16/92		
	10	EP	0 500 393 B1	EP	Akiyoshi Suzuki, et al.	08/26/92		
	11	EP	0 500 393 A3	EP	Akiyoshi Suzuki, et al.	08/26/92		
	12	EP	0 486 316 A3	EP	Naomasa Shiraishi	05/20/92		
	13	EP	0 496 891 A1	EP	Naomasa Shiraishi	08/05/92		
HW	14	EP	0 783 135 A1	EP	Akiyoshi Suzuki, et al.	07/09/97		

Examiner Signature	H. Nguyen	Date Considered	6/19/03

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

[1] Unique citation designation number. [2] See attached Kinds of U.S. Patent Documents. [3] Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). [4] For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. [5] Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible [6] Applicant is to place a check mark here if English language Translation is attached.

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 2 of 2

Complete if Known	
Application Number	TO BE ASSIGNED (DIV1)
Filing Date	March 8, 2002
First Named Inventor	Bruce W. Smith
Group Art Unit	2851
Examiner Name	Hung NGUYEN
Attorney Docket Number	81468.284420

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.[1]	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T[2]
HW	15	S. Asai, et al., "High Performance Optical Lithography Using a Separated Light Source", J. Vac. Sci. Technology, Vol B 10(6), pp. 3023-3026, (November/December 1992).	
	16	E. Tamechika, et al.,"Investigation of Single Sideband Optical Lithography Using Oblique Incidence Illumination", J. Vac. Sci. Technology, Vol. B 10(6), pp. 3027-3031, (November/December 1992).	
	17	W.N. Partlow, et al., "Depth of Focus and Resolution Enhancement for i-line and Deep-UV Lithography Using Annular Illumination", SPIE Optical/Laser Microlithography, Vol. 1927, pp. 137-156, (1993).	
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	22	Chin C. Hsia, et al., "Customized Off-Axis Illumination Aperture Filtering for Sub 0.18 um KrF Lithography", SPIE Optical Microlithography XI, Vol. 3679, pp. 39-46, (1999).	
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	24	Z. Yang, et al.,"Corrections of Aberrations Using HOE's in UV and Visible Imaging Systems", SPIE International Lens Deisgn Conference, Vol. 1354, pp. 323-327, (1990).	
HW	25	B. W. Smith, Microlithography: Science and Technology, Chapter 3, New York: Marcel Dekker (1998), pp. 216-231.	

Examiner Signature	H. Nguyen	Date Considered	6/19/03

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